



X301 **Anti-Stick Mask Coatings** **Cleaning Recommendations**

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Photronics **X301 Anti-Stick Mask Coatings** cleaning recommendations.

X-301 Mask Finish will withstand repeated cleanings with typical mask cleaning techniques. Acids, bases, and solvents combined with high pressure DI water, brush scrubbing with surfactant and spin or vapor dry are possible with this coating. The life of the coating could be reduced if very aggressive cleaning with high temperature acid is used.

The following simple cleaning process is very effective and will allow for a long lasting mask finish

- 1) Apply solvent or stripper for the removal of residual photoresist
- 2) Scrub the mask with a soft brush or sponge and a detergent with surfactant and then rinse with high purity water
- 3) Dry the mask using a spin process with N2 assist or use a vapor drying method

Preferred Chemicals

- Surfactants such as CA-40 from Cyantek
- Water
- IPA

Other Acceptable Chemicals*


- 10% KOH
- Sulfuric & Other Strong Acids
- Positive Photoresist Strippers & Other Strong Bases
- Acetone

* The effectiveness of the X-301 Mask Finish will decrease more quickly with the use of these chemicals.

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